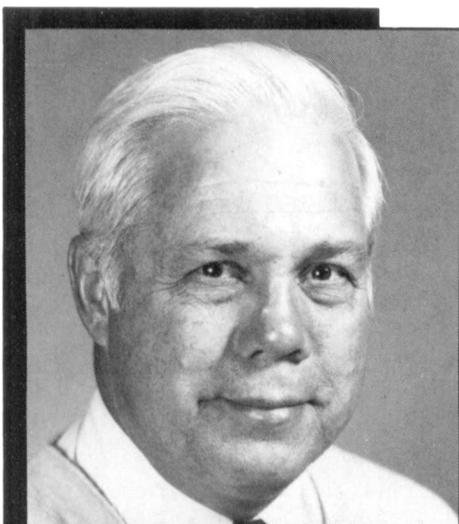


Associate Editors Gear Up to Facilitate Monthly Publication of *Journal of Materials Research*



Walter L. Brown
Editor-in-Chief, JMR

Werner Lutze and Shigeyuki Sōmiya, newly appointed Associate Editors of *Journal of Materials Research* (JMR), report that their editorial offices are now accepting manuscripts for consideration.

"I am pleased with the enthusiasm that both Dr. Lutze and Prof. Sōmiya have demonstrated in establishing a network of top-notch Principal Editors to assist them," said Editor-in-Chief Walter L. Brown. "Their commitment to helping JMR expand its communications links within the international materials community will further enhance JMR's coverage of important research in the coming months."

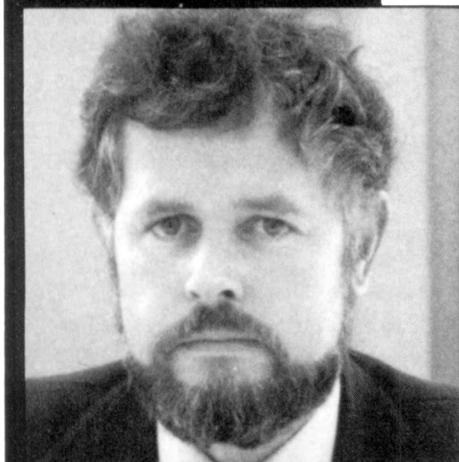
During the past five years, JMR has expanded rapidly in topical coverage, international exposure, and the number of published articles. The change to monthly publication of JMR in 1990 is a further reflection of this growth. To better accommodate JMR's expanding base of authors and provide rapid manuscript review, two new international Associate Editors, Dr. Werner Lutze in West Germany and Prof. Shigeyuki Sōmiya in Japan, were recently appointed by Walter Brown and 1989 MRS President Bob Chang.

Dr. Lutze, a JMR Principal Editor since 1986, joined Kernforschungszentrum Karlsruhe in January 1990 as head of a materials research group. He will also lecture at the Universität Karlsruhe. Lutze received his PhD in chemistry from the Technische Universität Berlin. His research interests include properties and structure of inorganic ion exchangers, glass and

glass ceramics, fusion reactor blanket materials, and radioactive waste management. He was organizer of both the fifth and twelfth symposia in the MRS series on the Scientific Basis for Nuclear Waste Management.

Prof. Sōmiya, previously a JMR Principal Editor, is professor emeritus at the Tokyo Institute of Technology and professor at the Teikyo University of the Nishi Tokyo University. His research interests focus on advanced ceramics. Sōmiya recently served as meeting chair for the MRS International Meeting on Advanced Materials held in Tokyo in 1988 and was involved in developing the newly formed MRS International Materials Research Committee. He also helped to establish the new Advanced Materials Science and Engineering Society in Japan, for which he is currently president.

In addition to Editor-in-Chief Walter L. Brown, Dr. Lutze and Prof. Sōmiya are responsible for the solicitation, acquisition, and review of JMR manuscripts. Through the efforts of these internationally based Associate Editors, manuscript acquisition and review, especially in Europe and the Far East, will be facilitated and accelerated. Authors now have the option of submitting manuscripts directly to Walter Brown through the JMR Editorial Office at MRS Headquarters in Pittsburgh or to Dr. Lutze or Prof. Sōmiya. However, it is anticipated that authors primarily in Europe and the Far East will find it convenient to send their manuscripts directly to the Associate Editor in their region. MRS



Werner Lutze
Associate Editor, JMR

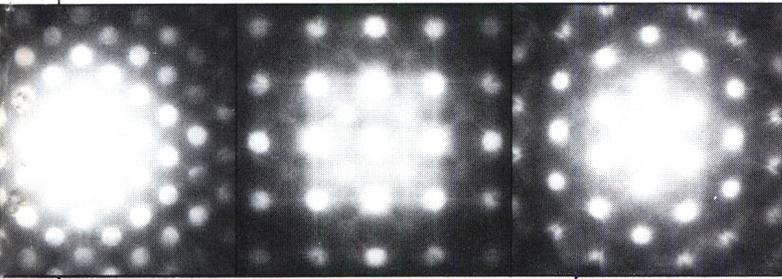


Shigeyuki Sōmiya
Associate Editor, JMR

Manuscripts for consideration in JMR can be sent to any one of the following:

- Dr. Walter L. Brown, Editor-in-Chief, Journal of Materials Research, Materials Research Society, 9800 McKnight Road, Pittsburgh, PA 15237; telephone (412) 367-9111
- Dr. Werner Lutze, Kernforschungszentrum Karlsruhe, Postfach 3640, D-7500 Karlsruhe, West Germany; telephone 49-7247-824457; fax 49-7247-823927.
- Prof. Shigeyuki Sōmiya, Nishi Tokyo University, 3-7-19 Seijo, Setagaya, Tokyo 157, Japan; telephone 81-3-417-2866; fax 81-3-415-6619.

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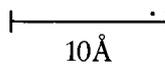
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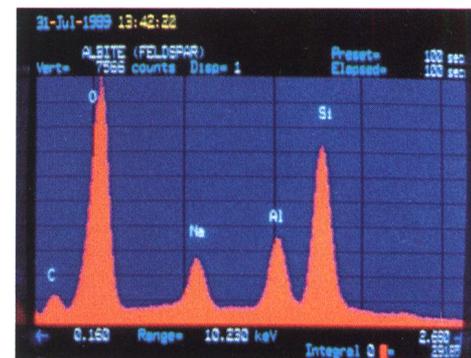
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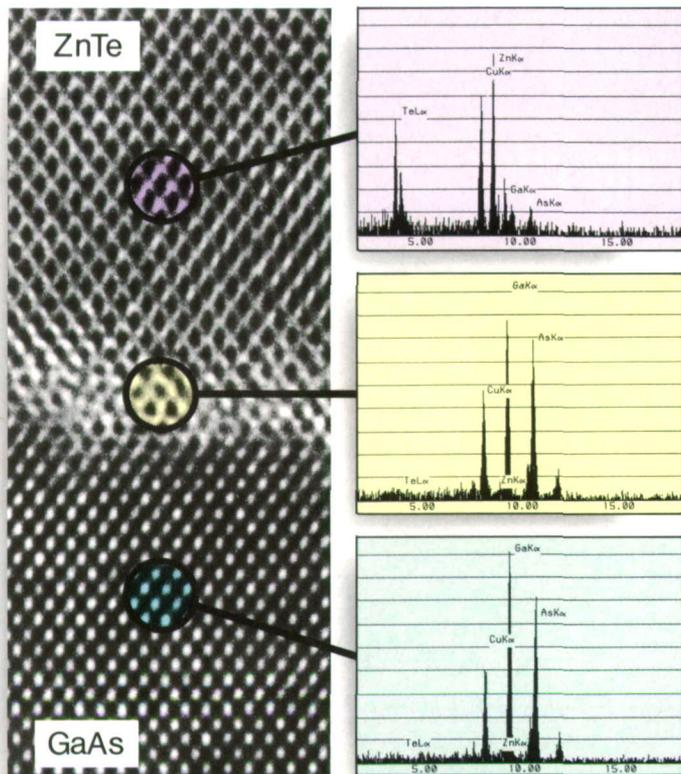
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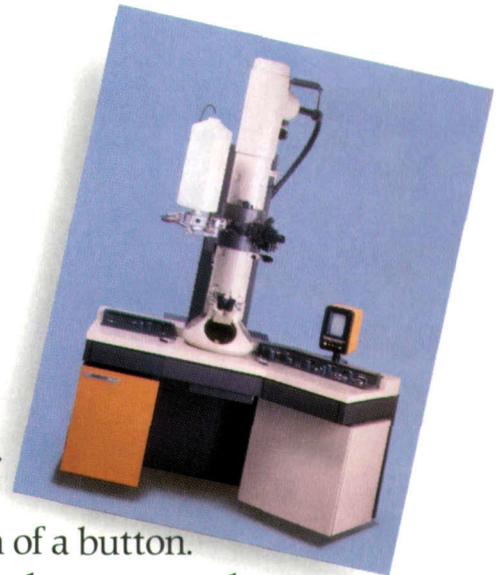
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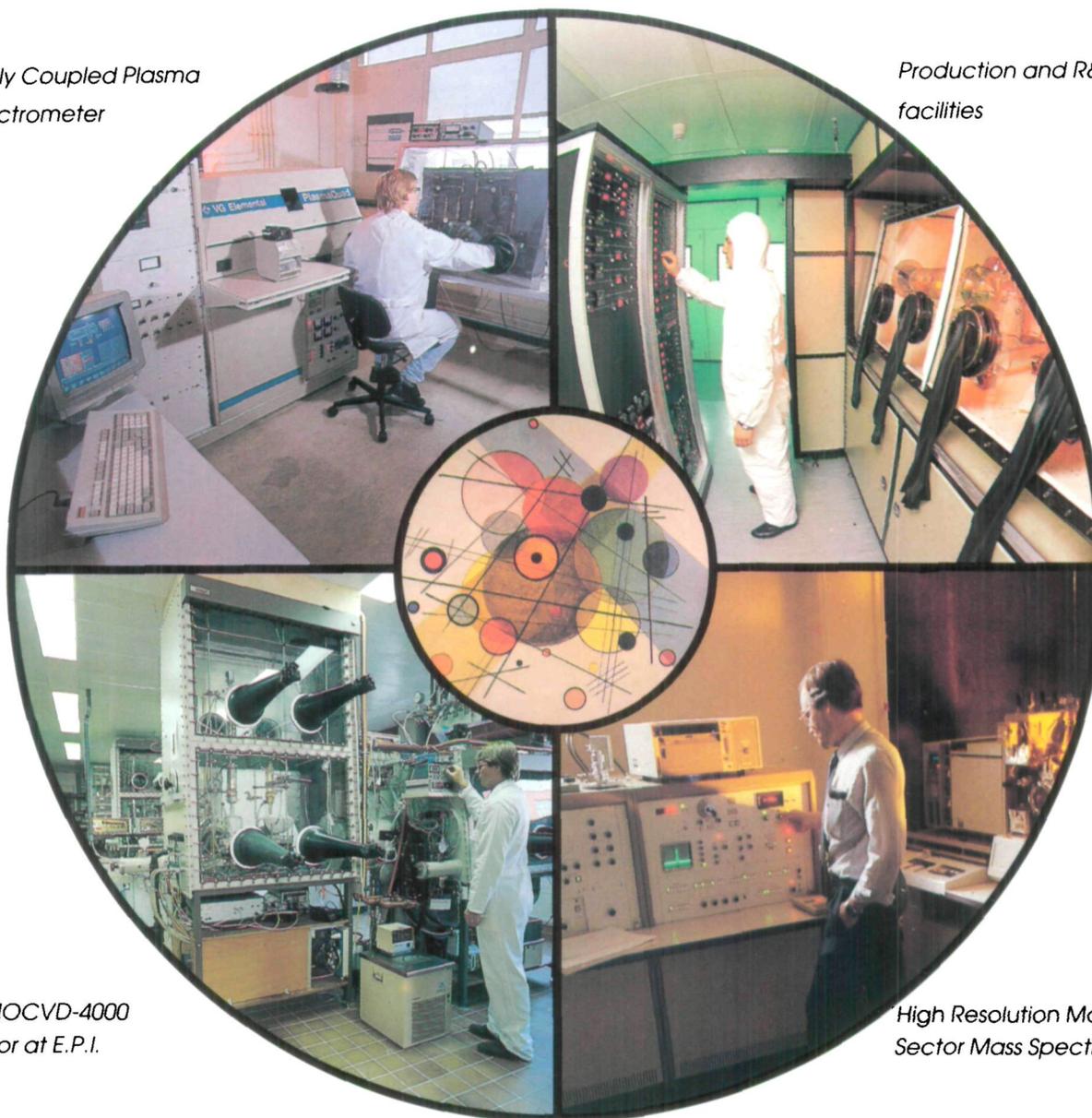


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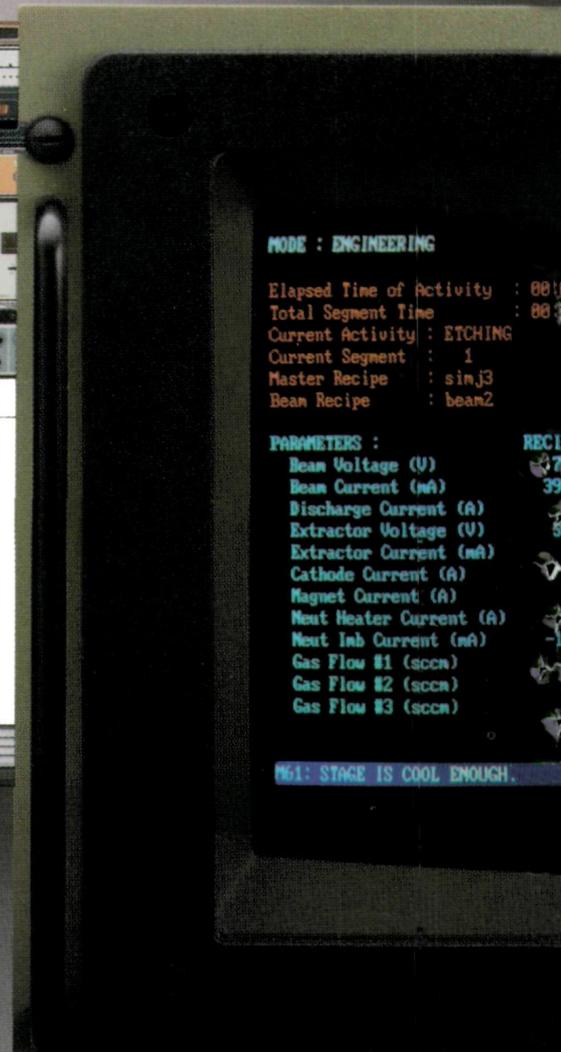
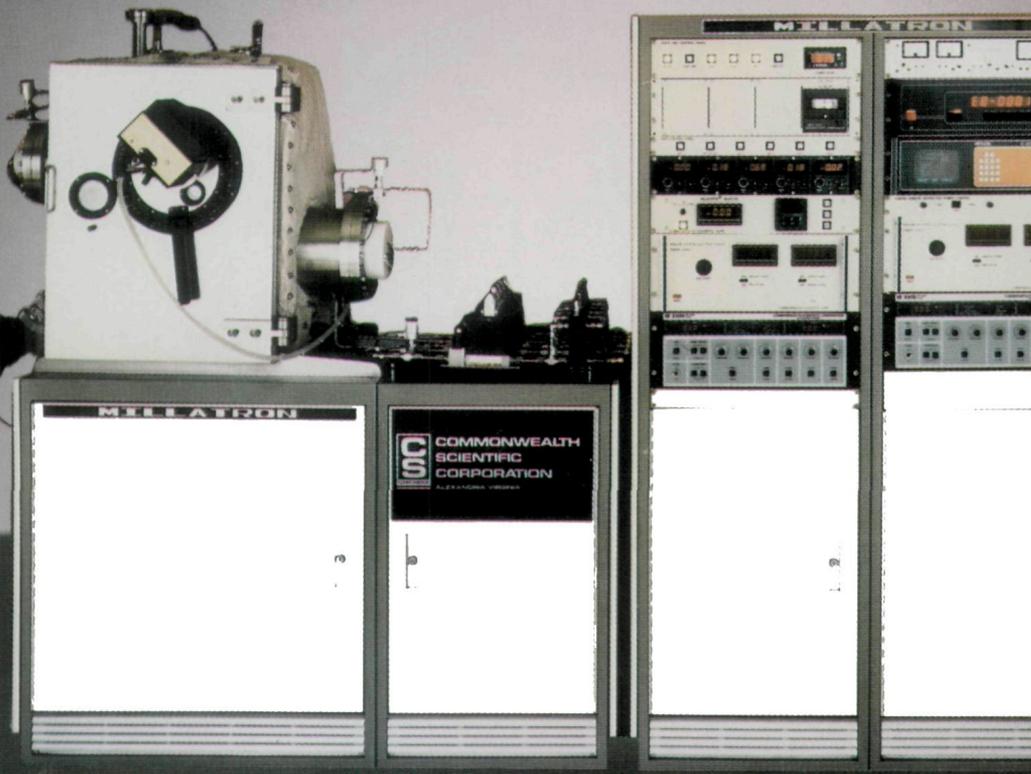
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